

# Towards the optimzation of the Cs evaporation configuration for long pulse operation in negative ion sources

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### **ELISE test facility**



- Cs evaporated to reduce plasma grid work function:
  - increase H-/D- production
  - decrease co-extracted electrons (limiting factor for long pulses in D<sub>2</sub>)

- Cs evaporation:
  - 2 Cs oven located on the sides of the ion source
  - Direction evaporation  $\rightarrow$  source back-plate



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#### **CsFlow3D Monte Carlo test-particle code**



#### VACUUM PHASE

- Only neutral Cs
- Ballistic transport ( $p \approx 10^{-4}$  Pa)
- Dynamics determined by:
  - Oven outflow profile
  - Source geometry
  - Wall sticking probability (temperature and impurities)

#### PLASMA PHASE

Beam pulse

- Both Cs neutrals and ions
- Collisions (p ≈ 0.3 Pa) :
  - Background gas
  - Plasma
- Cs redistribution by plasma
- Cs Sputtering by back-streaming ions



# **Consecutive long pulses: experiments vs. simulations**

- 3 consecutive pulses of 1 hour performed (15 mins vacuum in between)
- Strong reduction of neutral Cs density in the first 100 s
- Similar absolute value and trend for the simulations
- Increase of Cs in consecutive pulses (~ 30%): however, not enough for an improvement in the stability of co-extracted electrons.

Deuterium RF power 35 kW/driver Extraction voltage: 5 kV Acceleration voltage: 25 kV Ibias: 5A IPG: 3.8 kA







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  - Spider like oven between drivers











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• Depletion of Cs observed also with racetrack driver, but the different topology of plasma produces slightly higher fluxes



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- Depletion of Cs observed also with racetrack driver, but the different topology of plasma produces slightly higher fluxes
- Further increase of the Cs flux by evaporating with the top and bottom oven (direction of racetrack elongated side)
- Strongest depletion and lowest flux with the SPIDER-like oven positioned in between the racetrack drivers
- Overall, 50% increase of the Cs flux can be achieved. We can understand the mechanism by determining the originating surface for the Cs flux.















































# Alternative Cs evaporation concept: "Cs shower"



- Distributed Cs evaporation<sup>[1]</sup> close to the PG:
  - limit Cs ionization (no problem with PG bias voltage)
  - controllable evaporation of Cs where is needed
- Main idea: pipe with orifices around a beamlet group
- Test concept designed and developed for BATMAN Upgrade (special thanks to Markus Fröschle!)





54 orifices (27 on each side of the beamlet group) Ø 0.4 mm Pipe inner diameter 3 mm

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- Fast reaction of Cs shower: 10-15 s after opening the valve Cs is detected as well as impact on the performances
- Required Cs density for a significative stabilization of co-extracted electrons achieved



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- Further tests on uniformity of evaporation and reliability for the extension to larger sources ongoing.



### Conclusions



- Repetition of long pulses (1 hour) with the standard configuration shows a marginal increase of Cs flux but experiments shows no benefit in reducing co-extracted electrons: not enough Cs to counteract work-function degradation
- Optimization of location of the Cs oven for ELISE with racetrack driver: allow an increase of Cs flux and of the stability. However: always a depletion in time is observed and the majority of Cs is ionized
- Alternative evaporation concept: "Cs shower" close to the PG can avoid the problem of Cs ionization and of the plasma transport and can help in reducing Cs consumption:
  - Tested at BATMAN Upgrade: proved that additional Cs can stabilize co-extracted electrons
  - Further tests to assess **uniformity of evaporation**, impact on the high voltage system and **reliability** in routine operation in the view of **extending the concept to larger sources**